



Application Serial No. 09/677,478
Supplemental TDS

EV372471501

MI22-1544

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. 09/677,478
Filing Date October 2, 2000
Inventor Guy t. Blalock
Assignee Micron Technology, Inc.
Group Art Unit 1765
Examiner Lan Vinh
Attorney's Docket No. MI22-1544
Title: Plasma Etching Methods

To: Mail Stop RCE
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SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Reference -- See Attached Form PTO-1449

This Request for Continued Examination (RCE) Application is being filed in an abundance of caution to ensure consideration of the reference listed on the attached form PTO-1449.

The attached form PTO-1449 is submitted in compliance with 37 CFR §1.56. No admission is made regarding whether the submitted reference is prior art.

Respectfully submitted,

Dated: 11-23-04

By: D. Brent Kenady
D. Brent Kenady
Reg. No. 40,045

 Form PTO-144 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE LIST OF ART CITED BY APPLICANT <small>(Use several sheets if necessary)</small>		ATTY. DOCKET NO. MI22-1544		SERIAL NO. 09/677,478			
		APPLICANT Blalock et al.					
		FILING DATE October 2, 2000		GROUP 1765			
		U.S. PATENT DOCUMENTS					
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA	6,465,051 B1	10/02	Sahin et al.			
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						
FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	Translation
	AL						Yes
	AM						No
	AN						
	AO						
	AP						
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
	AR						
	AS						
	AT						
EXAMINER				DATE CONSIDERED			
<small>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609: Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</small>							